

# OVERVIEW FRAUNHOFER ENAS AND ZFM

Prof. Dr. Thomas Otto

Prof. Dr. Stefan Schulz

Prof. Dr. Karla Hiller



# In Memoriam Prof. Dr. Dr. Prof. h.c. mult. Thomas Gessner (\*10.08.1954 †25.05.2016)

- Studied physics, received diploma degree in 1979 and PhD degree Dr. rer. nat. in 1983 both from Dresden University of Technology, and Dr.-Ing. habil. degree from Technische Universität Chemnitz in 1989
- Since 1993, Professor for Microtechnology at Technische Universität Chemnitz
- Since 2007, Committee Chairman of the International Smart Systems Integration Conference and Exhibition
- Founding and Board Member of EPoSS e.V., the European Technology Platform on Smart Systems Integration
- Author of more than 900 publications and 136 patents filed in 48 patent families in microelectronics, micro systems and smart systems technologies



Director of Fraunhofer ENAS

Director of the Center for  
Microtechnologies at TU Chemnitz

Principle Investigator at WPI-AIMR at  
Tohoku University Sendai, Japan

# Smart Systems Campus Chemnitz

smart systems | campus  
TechnoPark Chemnitz



A – Institute of Physics and Center for Microtechnologies at the CUT

B – Fraunhofer ENAS

C – Start-up-building

D – Lightweight Structures Engineering

E – 3D-Micromac AG

F – Microflex Center Chemnitz (3D-Micromac AG, Fraunhofer ENAS)

G – MAIN

H – EDC Electronic Design Chemnitz GmbH

I – Competence Center IT and Catering

# Fraunhofer Institute for Electronic Nano Systems

**Director (acting):**  
**Deputy Director:**

**Prof. Dr. T. Otto**  
**Prof. S. Schulz**

**Rep. Office Manaus  
Brazil**

**Rep. Office Shanghai  
China**

**Rep. Office Tokyo/Sendai  
Japan**

**Multi Device  
Integration (OE 610)**  
**Prof. Otto**

**Printed Functionality  
(OE 630)**  
**Prof. Baumann**

**System Packaging  
(OE 650)**  
**Dr. Wiemer**

**Administration**  
**Mr. Höppner**

**Micro Materials  
Center (OE 620)**  
**Prof. Rzepka**

**Back-End  
of Line (OE 640)**  
**Prof. Schulz**

**Advanced System  
Engineering (OE 660)**  
**Dr. Hedayat**

# Main working fields ENAS and ZFM



## International Offices of Fraunhofer ENAS:

- |                 |                          |
|-----------------|--------------------------|
| Since 2001/2005 | Tokyo/Sendai, Japan      |
| → Since 2012    | Project-Center in Sendai |
| Since 2002      | Shanghai, China          |
| Since 2007      | Manaus, Brazil           |

## Systems integration by using of micro and nano technologies

- MEMS/NEMS design
- Development of MEMS/NEMS
- MEMS/NEMS test
- System packaging/waferbonding
- Back-end of Line technologies for micro and nano electronics
- Process and equipment simulation
- Micro and nano reliability
- Printed functionalities
- Advanced system engineering



# Center for Microtechnologies

**Chair Microsystems  
and Precision  
Engineering**  
Prof. Mehner

**Chair Circuit and  
System Design**  
Prof. Heinkel

**Chair Electronic  
Devices of Micro and  
Nano Technique**  
Prof. Horstmann

**Chair  
Microtechnology**  
Prof. Gessner

**Chair Power Electronics  
and Electromagnetic  
Compatibility**  
Prof. Lutz

**Chair Materials  
and Reliability of  
Microtechnical Systems**  
Prof. Wunderle

**Chair Electrical  
Measurement and  
Sensor Technology**  
Prof. Kanoun



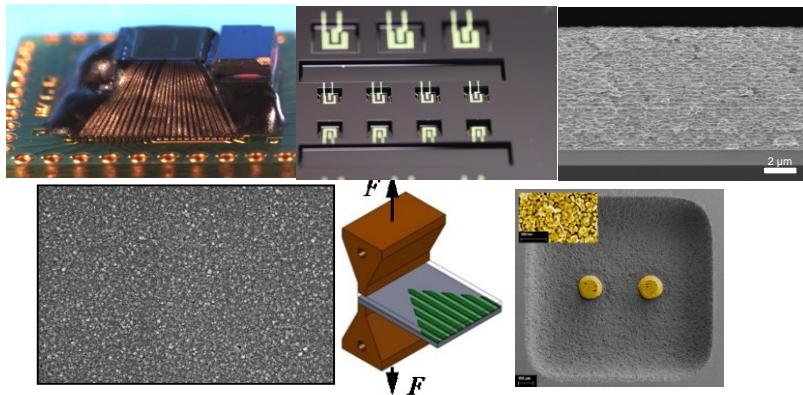
# Overview System Packaging

Head: Maik Wiemer

## Materials for MEMS (F. Roscher)

### Topics

- Nano Effects for Packaging
- Material Deposition for Packaging & MEMS
- Additive Technologies



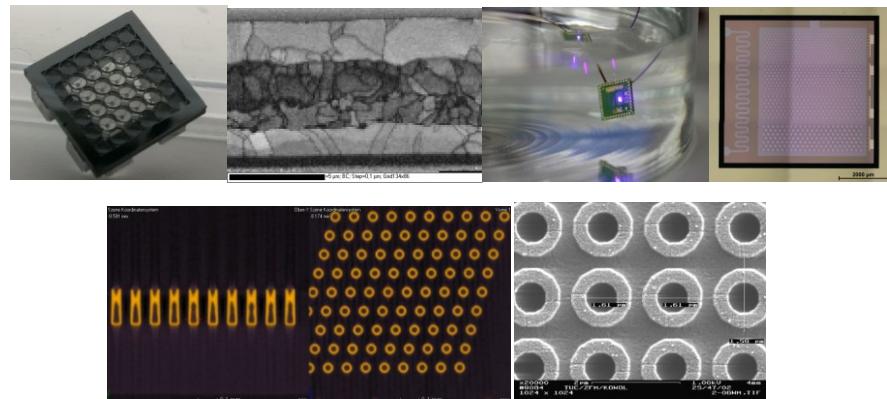
**Researchers (7):** Roscher, Seifert, Saeidi, Vogel, Hertel, Reich, Schröder

**Operator (3):** Kinner, Uhlig, Lesner,  
**Trainee (2):** Hebenstreit, Hellmann

## Integration Technologies (M. Baum)

### Topics

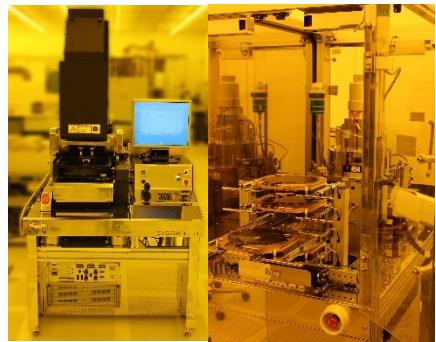
- Waferlevel und Chiplevel Packaging
- 3D Integration
- Devices & MEMS



**Researchers (5):** Baum, Wünsch, Hofmann, Wang, Selbmann

# SELECTED EQUIPMENT

## Permanent Wafer Bonding



Maskaligner: Wafer Bonder  
NT6200      EVG 540

## Thin Wafer Handling



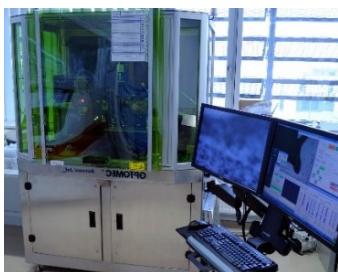
Grinder  
Disco  
DAG 810

## Electric Contact Formation



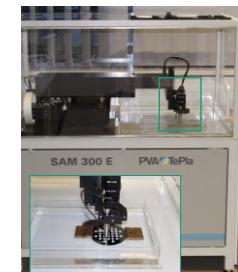
MOCVD:  
AMAT P5000

## Chip and Board Bonding

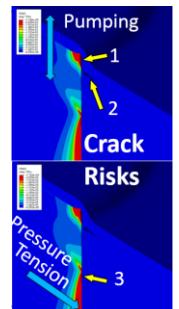


Aerosoljet

## Characterisation / Reliability

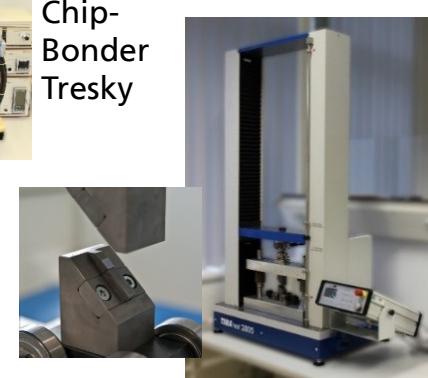


TePla SAM  
300E



Simulation for  
Reliability

## Chip-Bonder Tresky



Shertest TIRA-Test



Wafer Bonder  
SÜSS SB8e      Bondaligner:  
BA 6/8



De-Bonde  
r SÜSS  
DB12T



Electroplating: RENA (Fountain-Plater)  
und Ramgraber

# Wafer Bonding / MEMS Packaging

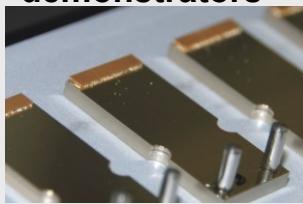
Smart integrated Systems

## Applications

With nano layers bonded demonstrators



### Flexible Substrates

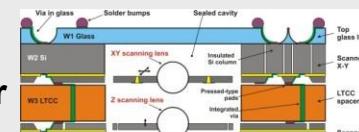
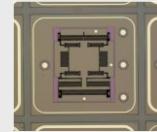


Plasma activated bonding for pressure sensors



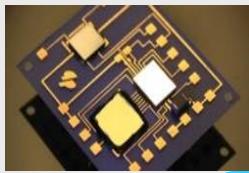
### Si-Interposer Integration

Hermeticity characterization with micro resonators

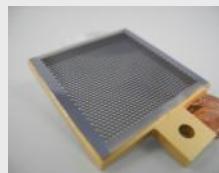


### Vertically integrated 3D microscanners

### iRMS

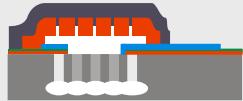


Interposer Integration

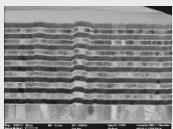


\* ZFM \* ENAS

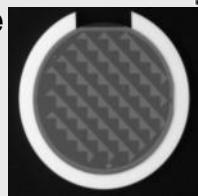
Nano Effects for Wafer Bonding



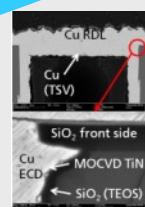
Thin film Encapsulation



low temperature Wafer Bonding



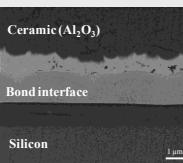
Foturan glass wafer bonding



Cu bonding with TSVs



SLID Bonding



New materials



Bio Packaging

Technologies

2008

2009

2010

2011

2012

2013

2014

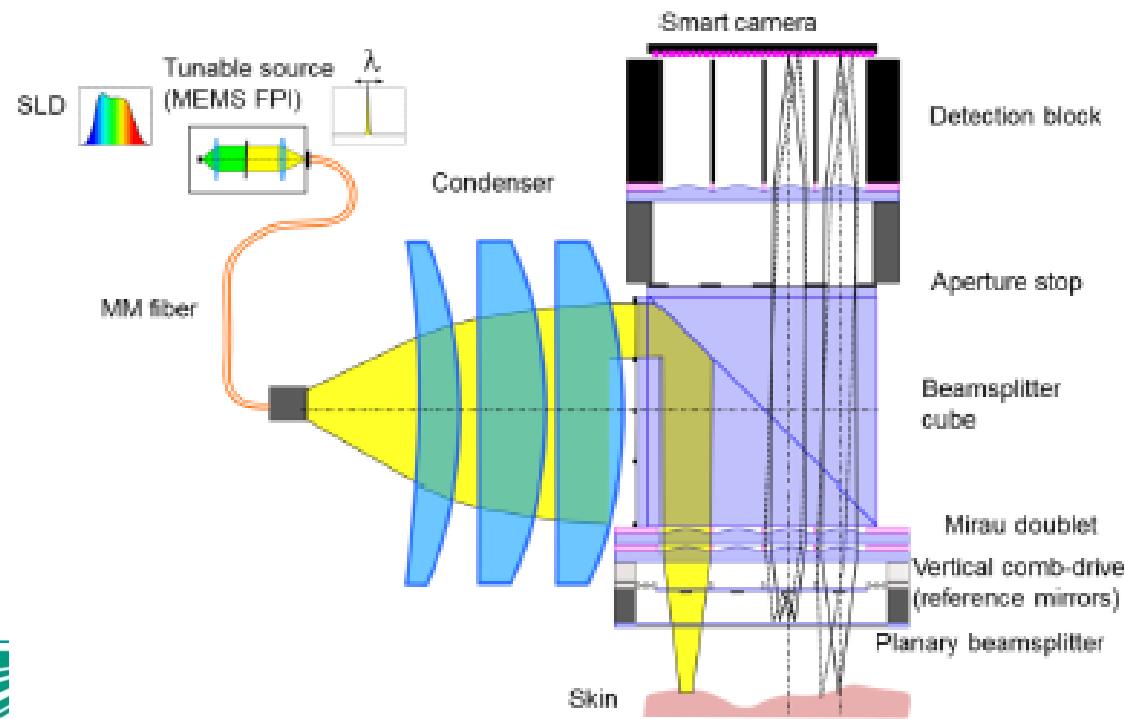
2015

2016

### Project content:

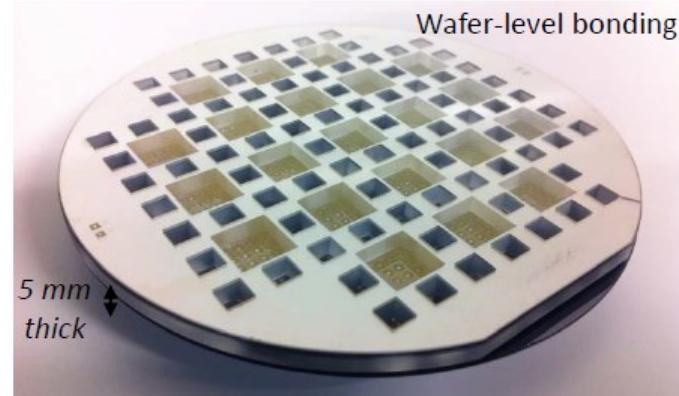
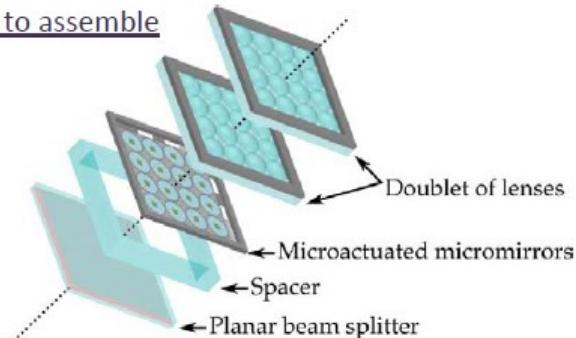
- The goal of VIAMOS is to benefit from advanced MOEMS technologies, enabling a new generation of miniature instruments. The challenge is to provide handheld, low-cost, fully parallel spectral domain miniature OCT devices (10 times cheaper, 150 times smaller), adapted for early diagnosis of cutaneous pathologies.
- Tasks of ENAS: Multi-wafer vertical assembly including functions for electric connections.

- Grant: EU FP7-ICT-2011-8,
- Term: 10/2012 – 03/2016
- Volume: 3.4Mio€ overall / 331k€ ENAS
- Partner: UFC-P5, CSEM, VTT, USTUTT, STAT, DERM

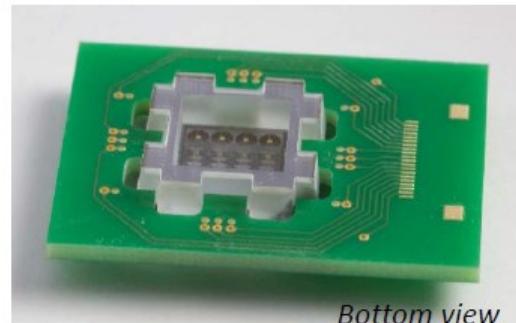
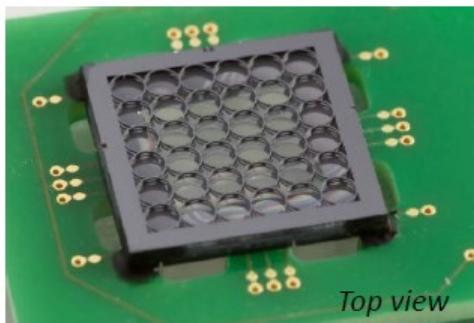


## Assembled Mirau $\mu$ -interferometer

7 wafers to assemble



Diced chips: 6 mounted on PCB (+2) have been delivered:



**Proc. of SPIE, vol. 9890,  
989011 (2016)**

Vertical integration of array-type miniature interferometers at wafer level by using multi-stack anodic bonding

Wei-Sian Wang<sup>a</sup>, Mark Wiemer<sup>a</sup>, Joerg Trossen<sup>a</sup>, Tom Endlein<sup>a</sup>, Thomas Gessner<sup>b</sup>, Jasine Lüttin<sup>c</sup>, Sylvester Burge<sup>c</sup>, Nicolas Passilly<sup>d</sup>, Jorge Albero<sup>d</sup>, and Christophe Gorecki<sup>d</sup>  
<sup>a</sup>Trafohofer Institute for Electronic Microsystems, Technologie Campus 3, 69126 Chemnitz, Germany; <sup>b</sup>Fachhochschule Chemnitz, 09107 Chemnitz, Germany; <sup>c</sup>FEMTO-ST Institute, 15B, Avenue des Montboucons, F-25050 Besançon, France

### ABSTRACT

In this work, vertical integration of miniaturized array-type Mirau interferometers at wafer level by using multi-stack anodic bonding is presented. Mirau interferometer is suitable for MEMS technology and for medical imaging according to its vertical integration and its working principle. Miniature Mirau interferometer can be a promising candidate as a key component for an optical coherence tomography (OCT) system. The miniaturized array-type interferometer consists of a micro-lens doublet, a 5-lenslet MEMS Z-sensor, a spacer for focus-adjustment and a beam splitter. Wafer-level bonding technologies which are suitable for heterogeneous substrate use of back-etched and

# Al-deposition by ionic liquids to replace typical metallisation processes used in information and communication technologies

## „AioLi“

- Grant-aided by
  - BMBF, IKT 2020
- Duration
  - 10/2015 – 03/2018
- Volume proposed
  - 1,8 Mio€ overall / 631 k€ SP
  - 40 MM R&D
  - 4 MM Operator
  - 18 MM Student (10 MM without Bachelor, 8 with Bachelor à 25h/month)



### Short Project Overview

- Synthesis of novel ionic liquids for ECD of aluminium on different substrate materials
- Extensive investigations of the processability of deposited Al with the technologies of electrical engineering and packaging
- Aim: Development of an ECD process of Al including deposition equipment and evaluation of various demonstrators in the fields of automotive, industry electronics, medical and telecommunication

# First results „AiOLi“

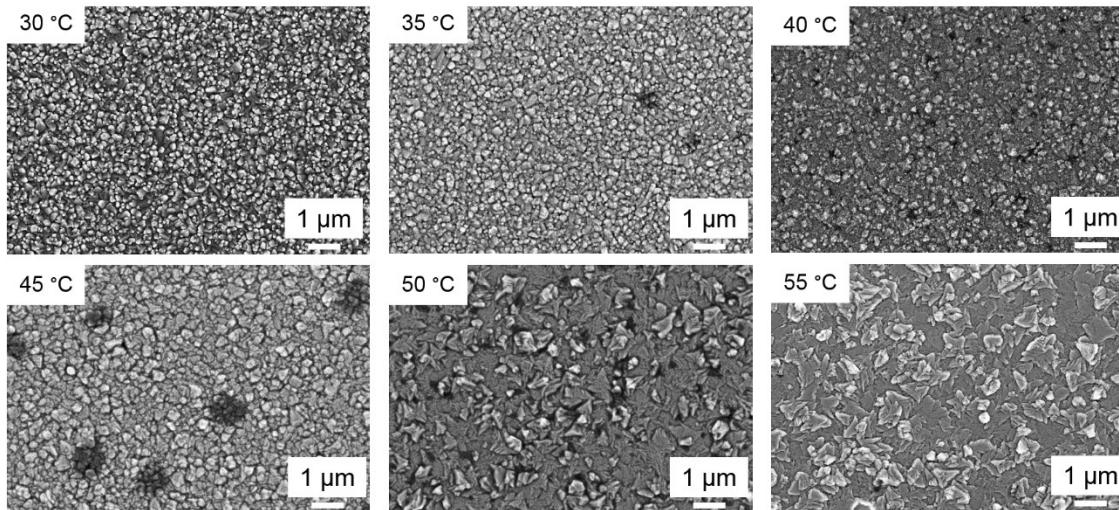


Fig. 1: SEM images of electrochemical deposited Al layers at different temperatures: Temperature of the ionic liquid influence the Al microstructure: increased temperature results in increased grain sizes

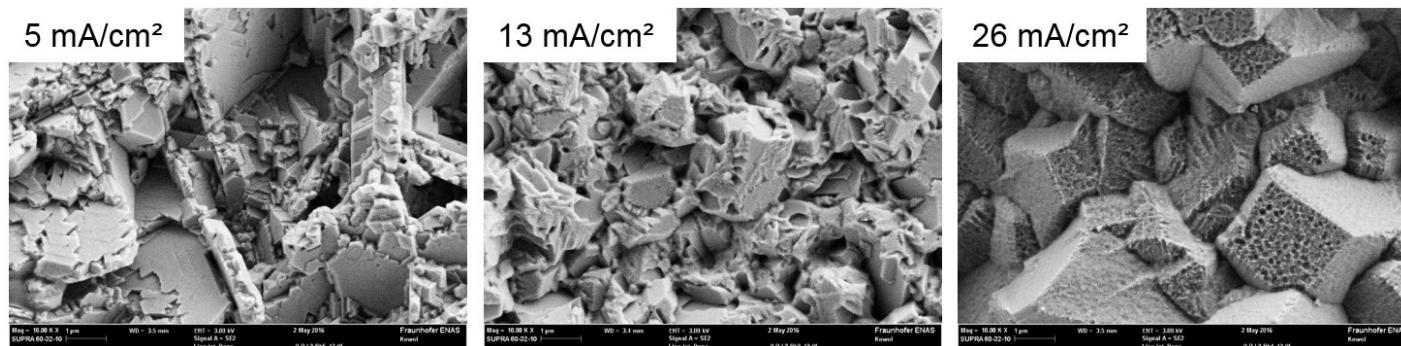


Fig. 2: SEM images of Al layers deposited at different current densities and constant temperature: 5 mA/cm<sup>2</sup>: floe like microstructure; 26mA/cm<sup>2</sup>: tapered shape microstructure → higher current densities results in cubic, tapered shape Al grains

# First Day – Tuesday June 14, 2016

Time		Speaker	Company	Titel
from	to			
1:00	1:20	M. Wiemer	Fraunhofer ENAS	Welcome note, Introduction to ENAS and Department System packaging
1:20	1:50	Prof. Jong Min Kim	University of Cambridge	Nanotechnology for its Convergence and Applications
1:50	2:20	Dr. Martin Eibelhuber	Dr. Martin Eibelhuber, EV Group E. Thallner GmbH	Developments, Applications and Challenges for the Industrial Implementation of Nanoimprinting Lithography
2:20	2:50	Dr. Wei-Shan Wang	Fraunhofer ENAS	Vertically-integrated array-type miniature interferometer as a core optical component of a coherence tomography system for tissue inspection
2:50	3:20	Tilo Borchardt	Tilo Borchardt, GETEMED Medizin- und Informationstechnik AG	Mobile Medical Devices for the Internet of Things – Design Challenges
3:20	3:50	Coffee break and networking		
3:50	4:20	Jens Heese	Jens Heese, Hansaton Akustik GmbH	Actual Hearing Aid Technologies – Technical innovations on smallest space
4:20	4:50	Dr. Tobias Liese	Siegert Thinfilm Technology	NiC: a new functional layer with high sensitivity for pressure and force sensors
4:50	5:20	Ronny Neubert	Microsensys	Separation of SiC Wafer Using Thermal Laser Separation
5:20	5:40	Dr. Reza Bahmanyar	Imperial College London	Implantable Pressure Sensors

# Second Day – Wednesday June 15, 2016

Time		Speaker	Company	Titel
from	to			
09:00	09:10	M. Wiemer	Fraunhofer ENAS	Welcome
09:10	09:40	Dirk Wünsch	Fraunhofer ENAS	Temporary Wafer Bonding – Key technology for 3D MEMS Integration
09:40	10:10	Dr. Steffen Kröhnert	NANIUM S.A.	Beyond State-of-the-Art: Integration of MEMS in Fan-Out Wafer-Level Packaging Technology based System-in-Package (WLSiP)
10:10	10:40	Dr. Srdjan Krco	DUNAV NET	TagItSmart - Creating IoT for mass market products
10:40	11:10	Frank Roscher	Fraunhofer ENAS	Printing of Electrical Functional Structures by using Aerosol-Jet
11:10	11:40	Coffee break		
11:40	12:10	Sebastian Hahn	PacTech – Packaging Technologies GmbH	Solder Jetting, Rework & Electroless UBM Deposition Made in Germany
12:10	12:40	Maaike M. Visser Taklo	SINTEF ICT Instrumentation Dept.	Soldering of MEMS and Silicon Interposers: The Role of Intermetallic Compounds
12:40	1:10	Dr. Matthias Domke	Microtech Gefell GmbH	Design and Applications of Linear Microphone Arrays
1:10	1:40	Pieter Vandewalle	KLA-Tencor GmbH	How Can Process Control Help to Increase Yield for Advanced Packages like WLCSP, SIP, FO-WLP?
1:40				Closing remarks and lunch

# Contact us

Fraunhofer ENAS

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